

Workshop: Advances in Plasma Technology for Device Fabrication, Quantum, and more

27 July 2023

Venue: University of Washington, Alder Hall, 1315 NE Campus Pkwy, Seattle, WA 98105

Topics & Speakers

Time	Topic	Speaker
10:00 – 10:15	Welcome note & Registration	
10:15 – 10:30	Introduction to Oxford Instruments Plasma Technology	<i>Emiel Thijssen, Oxford Instruments</i>
10:30 – 11:00	Slanted Grating Etch for Augmented Reality	<i>Sebastien Pochon, Oxford Instruments</i>
11:00 – 11:30	An Overview of Plasma Etch for Compound Semiconductor Materials	<i>Katie Hore, Oxford Instruments</i>
11:30 – 12:00	An Overview of ICP Chemical Vapor Deposition	<i>Agnes Kurek, Oxford Instruments</i>
12:30 – 12:30	LUNCH BREAK	
12:30 – 13:10	Introduction to Quantum Device Fabrication	<i>Russ Renzas, Oxford Instruments</i>
13:10 – 13:30	ALD and DSiE for Superconducting Circuits	<i>Russ Renzas, Oxford Instruments</i>
13:30 – 14:00	Atomic Layer Etch (ALE) of Wide Bandgap & Color Center Materials	<i>Julian Michaels, University of Illinois at Urbana-Champaign</i>
14:00 – 14:05	Closing Remarks	<i>Emiel Thijssen, Oxford Instruments</i>

